L Number	Hits	Search Text	DB	Time stamp
-	1477	438/733.ccls. 438/780.ccls. 438/789.ccls. 438/790.ccls.	USPAT	2004/03/22 09:32
		438/725.ccls.		
-	2469	438/733.ccls. 438/780.ccls. 438/789.ccls. 438/790.ccls.	USPAT;	2004/03/15 10:14
		438/725.ccls.	US-PGPUB;	
			EPO; JPO	
-	798	(438/733.ccls. 438/780.ccls. 438/789.ccls. 438/790.ccls.	USPAT;	2004/03/15 00:15
		438/725.ccls.) and polymer	US-PGPUB;	
			EPO; JPO	
-	70	(CH2F2 difluoromethane) and (C4F8 "cyclic	USPAT;	2004/03/15 09:15
		octafluorobutane" octafluorobutane)	US-PGPUB;	, ,
		,	EPO; JPO	
-	564	(CH2F2 difluoromethane) and (CHF3 trifluoromethane)	USPAT;	2004/03/15 09:27
		(,	US-PGPUB;	
			EPO; JPO	
-	608	((CH2F2 difluoromethane) and (C4F8 "cyclic	USPAT;	2004/03/15 09:16
	000	octafluorobutane" octafluorobutane)) ((CH2F2	US-PGPUB;	200 1, 00, 15 05 120
		difluoromethane) and (CHF3 trifluoromethane))	EPO; JPO	
-	38	(((CH2F2 difluoromethane) and (C4F8 "cyclic	USPAT;	2004/03/15 09:27
	30	octafluorobutane" octafluorobutane)) ((CH2F2	US-PGPUB;	2001/03/13 03.27
		difluoromethane) and (CHF3 trifluoromethane)) ) and	EPO; JPO	
		(pecvd)	Li 0, 3i 0	
-	36	((CH2F2 difluoromethane) and (CHF3 trifluoromethane)) and	USPAT;	2004/03/15 09:27
	30	((((CH2F2 diffuoromethane) and (C4F8 "cyclic	US-PGPUB;	2004/03/13 03.27
		octafluorobutane" octafluorobutane)) ((CH2F2	EPO; JPO	
			EPO, JPO	
		difluoromethane) and (CHF3 trifluoromethane)) ) and		
-	26	(pecvd))	USPAT;	2004/03/15 09:46
	36	((((CH2F2 diffuoromethane) and (C4F8 "cyclic	US-PGPUB;	2004/03/13 03.40
		octafluorobutane" octafluorobutane)) ((CH2F2		
		difluoromethane) and (CHF3 trifluoromethane)) ) and	EPO; JPO	
	20	(pecvd)) and (CHF3 trifluoromethane)	LICDAT	2004/02/15 00:46
•	20	polymer adj2 over adj2 photoresist	USPAT;	2004/03/15 09:46
			US-PGPUB;	
	2245	420/722I- 420/700I- 420/700I- 420/700I-	EPO; JPO	2004/02/15 10:15
-	2215	438/733.ccls. 438/780.ccls. 438/789.ccls. 438/790.ccls.	USPAT;	2004/03/15 10:15
		438/725.ccls. and (contact "via plug")	US-PGPUB;	
		l and warm and all the second	EPO; JPO	2004/02/45 40:45
-	7754	polymer same photoresist	USPAT;	2004/03/15 10:15
			US-PGPUB;	
	4700	undi manu adi 2 mbatawa int	EPO; JPO	2004/02/45 40:45
-	1700	polymer adj3 photoresist	USPAT;	2004/03/15 10:15
			US-PGPUB;	
			EPO; JPO	2004/02/45 40 45
• •	47	(polymer adj3 photoresist) and (438/733.ccls. 438/780.ccls.	USPAT;	2004/03/15 10:15
		438/789.ccls. 438/790.ccls. 438/725.ccls. and (contact "via	US-PGPUB;	
		plug"))	EPO; JPO	2004/20/12 11 15
•	1390	29/830.ccls. 29/852.ccls.	USPAT	2004/03/19 11:12
	1034	29/846.ccls.	USPAT	2004/03/19 11:14
	842	29/825.ccls.	USPAT	2004/03/19 11:14
·	608	216/2.ccls.	USPAT	2004/03/19 11:16
·	163	216/37.ccls.	USPAT	2004/03/19 11:16
•	3882	29/829.ccls. 29/830.ccls. 29/852.ccls. 29/846.ccls.	USPAT	2004/03/22 09:34
		29/825.ccls. 216/2.ccls. 216/37.ccls.		